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Abstract: (Figs. 4A to 4D)

"METHOD AND APPARATUS FOR MANUFACTURING A LIQUID CRYSTAL DISPLAY SUBSTRATE, AND APPARATUS AND METHOD FOR EVALUATING SEMICONDUCTOR CRYSTALS"

An amorphous silicon film (2) is formed on a glass substrate (1) by a CVD method, and then the island regions of the amorphous silicon film is changed to a plurality of polycrystalline silicon regions (21) which are arranged in a line and apart with each other in a predetermined distanced by intermittently irradiating laser pulses each having the same dimensions as those of the island region onto the amorphous silicon film, using a laser beam irradiating section (3). Switching elements including the island regions (21) as semiconductor regions are formed by etching and film-forming process to constitute a driving circuit section (4). The section (4) is divided to gate driving circuit sections (41) and source driving circuit sections (42) for driving thin film transistors formed in a pixel region (50).